Supplementary Material

Design of metalized polyether-ether-ketone based on semi-additive manufacture

for 5G applications: From bottom-up assembly to selectively electroplating.

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Figure S1. Optical photographs of PEEK-Ni and PEEK-Cu after 3M test.



Figure S2. (a) SEM image of PEEK-Ni surface, SEM-EDX distribution of (b) nickel and (c) phosphorus.



Figure S3. Molecular structure of GPTMS.



Figure S4. Temperature change along simulation time in MD simulation.



Figure S5. Potential energy change along simulation time in MD simulation.

Table 51. Composition of 14 plating bain solution		
Chemical reagent concentration		
NiSO4@6H2O	25 g/L	
NaH ₂ PO ₂	25 g/L	
$Na_4P_2O_7$	50 g/L	
stabilizer A	trace	
surfactant B	trace	
NH ₃ © H ₂ O	adjust pH=10~11	

Table S1. Composition of Ni plating bath solution

Table S2. Fukui functions for GPTMS structure.

Atom		f^{-}		f^+
O-1	0.090	0,031	0.005	Choos
C-2	0.014	0.045 0.090	0.005	0005
C-3	-0.005	0.112 -0.025	0.008	0,013 0002
C-4	-0.025	255	0.002	0,033
O-5	0.255	0.106 0.027 0.080 0.102	0.000	0,087 0004
C-6	-0.009	0,005 0.018 0,009 (0,007	-0.073	0)994 0)996 0,059 0,0650047 0,073
Si-7	0.016	0,000 0,011 0,018 0,007 0,000 0,013 0,007 0,001	0.099	C.053 0.048 0.053 0.053
O-8	0.017	0,007	-0.035	00/0 0/28 0018 035 0,049
O-9	0.008	0.0050.001	-0.018	0.079 0.011 0.061
O-10	0.013	Cont C	-0.048	~

Note: In the illustration, the green arrow indicates the atom with the largest electrophilic attack index, and the red arrow indicates the atom with the largest nucleophilic attack index.